

## **ELECTRONIC INFORMATION DISCLOSURE STATEMENT**

Electronic Version v18 Stylesheet Version v18.0

> Title of Invention

FORMING A SUBSTANTIALLY PLANAR UPPER SURFACE AT THE OUTER EDGE OF A SEMICONDUCTOR TOPOGRAPHY

**Application Number:** 

10/662636

**Confirmation Number:** 

9393

First Named Applicant: Venuka Jayatilaka

Attorney Docket Number: 5298-04301

Search string:

(5783482 or 6472291 or 6376363 or 5918139 or 4193226 or 4811522 or 5421769 or 6010964

or 6091130 or 6020639 ).pn.

**US Patent Documents** 

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
9/6	1	5783482	1998-07-21	Lee et al.	*	438	624
918	2	6472291	2002-10-29	Page et al.	1 1	438	4/24
949	3	6376363	2002-04-23	lguchi	1 1	138	333
WB	4	5918139	1999-06-29	Mitani et al.	i / '	138	459
WB	5	4193226	1980-03-18	Gill, Jr. et al.	45	1	2 <b>7</b> 8
WE	6	4811522	1989-03-14	Gill, Jr.	45	1	285
W.B.	7	5421769	1995-06-06	Schultz et al.	\ - '	451	285
9/0	8	6010964	2000-01-04	Glass		156	345.12
% B	9	6091130	2000-07-18	Oyamatsu et al.	i }	257	, [
% <u>@</u>	10	6020639	2000-02-01	Ulrich et al.	\ <u>\</u>	257	73'

## Signature

Examiner Name	Date		
William M. Brunter	17 APR 86		

Form PTO-1449 (modified) ATTY. DKT. NO. 5298-04301 SERIAL NO. 10/662.636 List of Patents and Publications APPLICANT: Jayatilaka et al. **GROUP: 1765** For Applicant's Information Disclosure Statement FILING DATE: September 15, 2003 (Use several sheets if necessary) **U.S. PATENT DOCUMENTS** REF. **DOCUMENT NUMBER** DATE NAME CLASS FILING DATE IF EXAM. SUB APPROPRIATE **CLASS INITIALS** DES. **FOREIGN PATENT DOCUMENTS** TRANSLATION DATE CLASS REF. DOCUMENT NUMBER COUNTRY EXAM. **SUB** YES/NO DES. **INITIALS CLASS** OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) Malkoe et al., "Effect of Retaining Ring System on the Polishing of 300 mm Oxide Wafers," March **A1** 913 2001, pp. 519-522. Wolf, Silicon Processing for the VLSI Era, Volume 2: Process Integration, © 1990 by Lattice Press, **A2** WB pp. 238, 239.

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the patent owner.

EXAMINER: gralliam M. Brenten

DATE CONSIDERED: 17 A PR AG